

Feature

- Precision MEMS process
- High performance, shielded, Micro-cavity structure
- Silicon substrate, 50Ω CPW output
- Au wire bonding, for MCM applications

Environmental Specifications

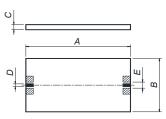
Operating Temperature	-55℃~+85℃	
Storage Temperature	-55°C~+125°C	
Max. Input Power	35dBm	

Electrical Specifications(T_A=+25°C)

Parameter	Min.	Тур.	Max.	Unit
Center Freq. (f₀)	-	15.2	-	GHz
Pass Band	14.7	-	15.8	GHz
Ripple in Pass band	-	-	1	dB
Insertion Loss @ f₀	-	-	2.0	dB
Return Loss	15	-	-	dB
Out of band	≥30@13.8GHz&16.6GHz			dB
Attenuation	≥40@13.4GHz&16.75GHz			dB
Group Delay Variation	≤0.5@14.7~15.8GHz ≤±7@14.7~15.8GHz			ns
Linear Phase				0

S2P file name: SiMS15R2_1-6D2.s2p

Outline Drawing

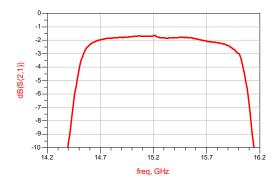


■I/O PORT 図GOLD/GROUND

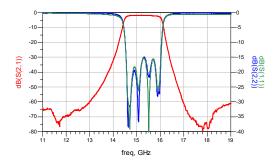
Symbol		Value (mm)	l
	Min.	Nominal	Max.
А	7.9	-	8.0
В	3.7	-	3.8

Typical Test Curves

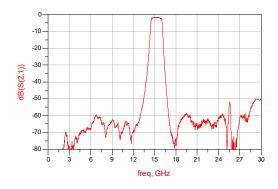
Insertion Loss VS Frequency (T_A=25°C)



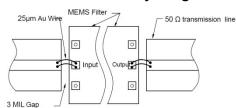
Insertion Loss & Return Loss VS Frequency (T_A=25°C)



Broadband Insertion Loss VS Frequency (T_A=25°C)

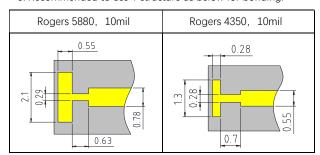


Recommended Assembly Diagrams



Application Notes:

- 1. The chip is back-metalized and can be die mounted with AuSn eutectic performs or with electrically conductive epoxy (for example ME8456).
- 2. The die should be assembled on carriers like Kovar or Mu-Cu which have same Coefficient of thermal expansion. (2.9ppm/ $^{\circ}$ C) with Silicon, thickness 0.2mm max.
- 3. Handle the chips in a clean environment. DO NOT attempt to clean the chip using liquid cleaning systems.
- 4. Handle the chip along the edges with a vacuum collet or with a sharp pair of bent tweezers.
- 5. Recommended to use T structure as below for bonding.



6. If you have any questions, please contact us.